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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE
Patent ApplicationInventor(s): Fan Zhong and Jonathan G. Bornstein Group Art
Unit:

Filed: 06/04/01

Examiner:

Serial No.: 09/874,434

Title: METHOD AND SYSTEM FOR A HIGH-DENSITY PLASMA DEPOSITION PROCESS FOR
FABRICATING A TOP CLAD FOR PLANAR LIGHTWAVE CIRCUIT DEVICES

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U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
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Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation
	L						Yes No
	M						
	N						
	O						
	P						
	Q						

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	R	
	S	
	T	
Examiner	Joc S. Fortune	
	Date Considered 9/9/03	

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered.
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